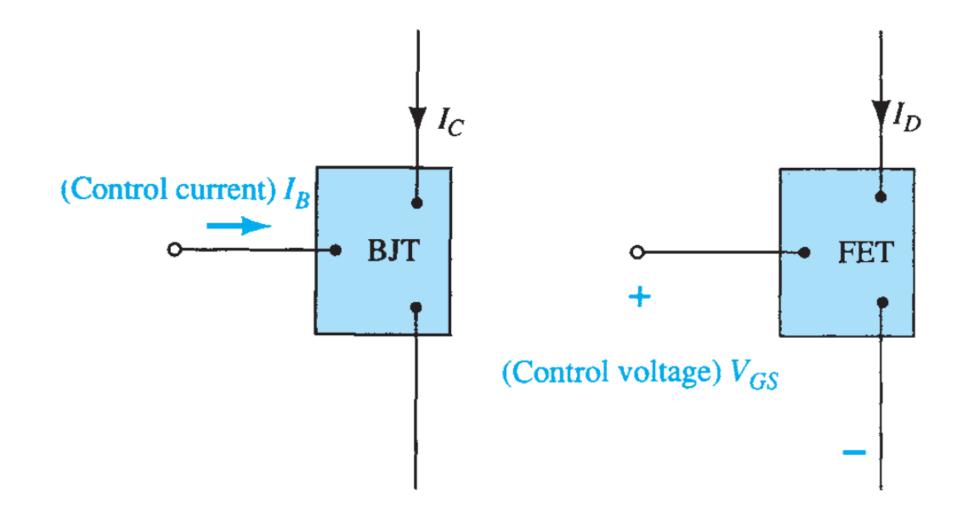
Field-effect transistor (FET)

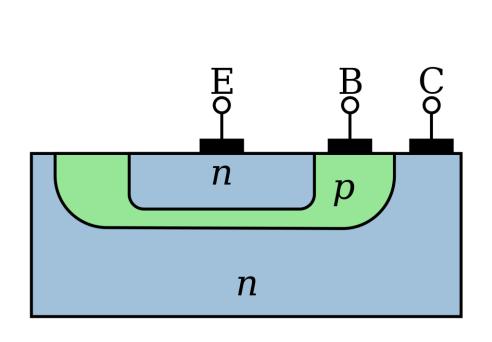
Dr Mohammad Abdur Rashid

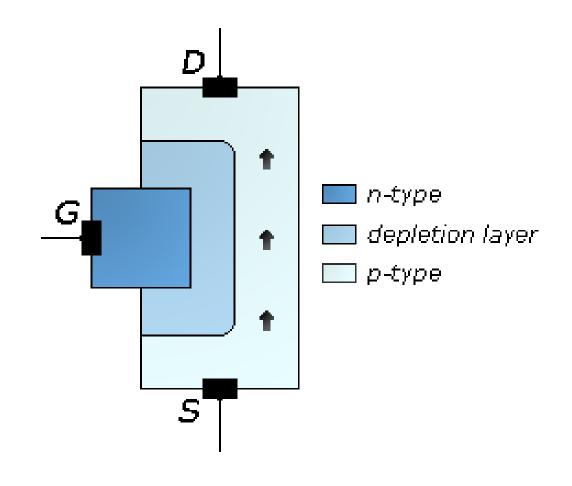


BJT and FET

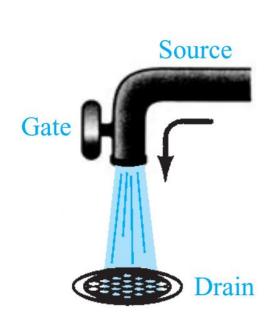


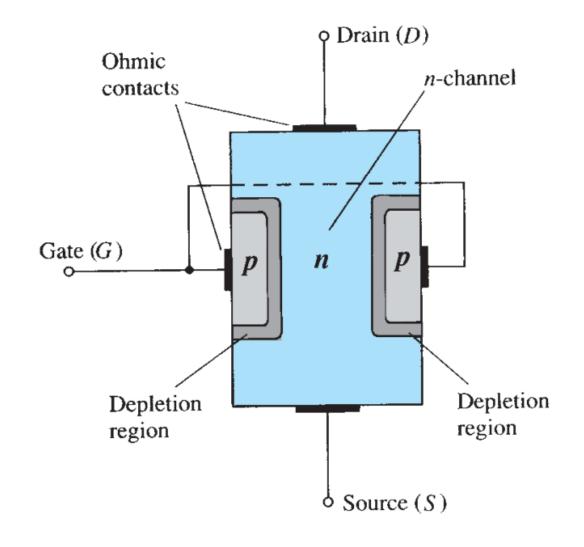
BJT and FET





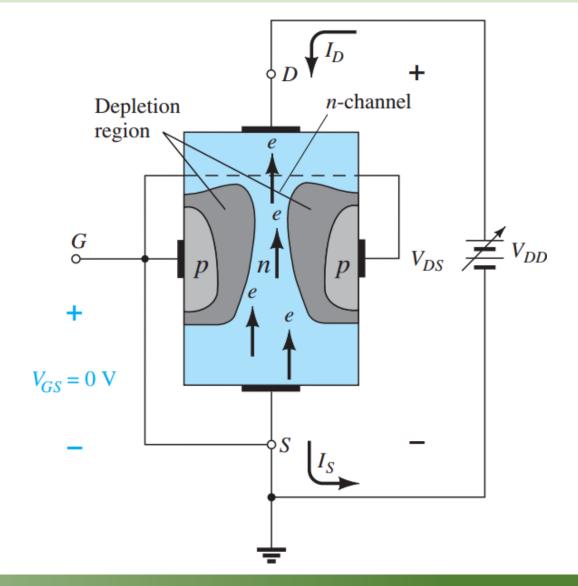
Junction field-effect transistor (JFET)



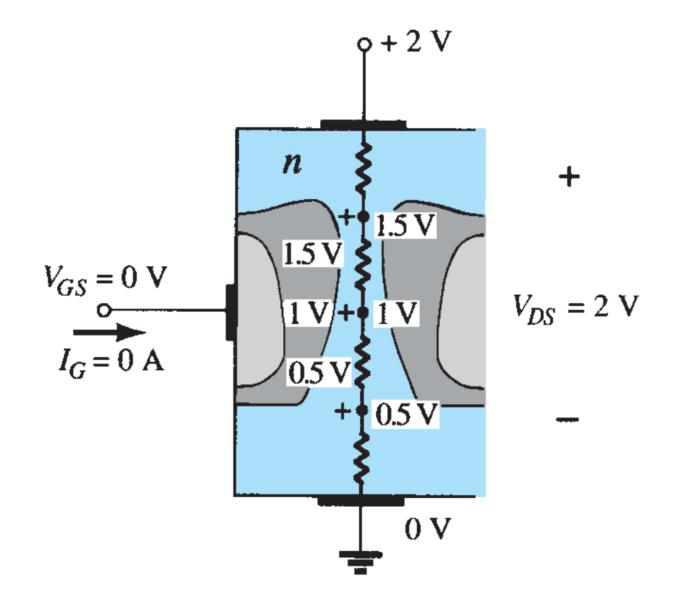


Flow of charge in JFET

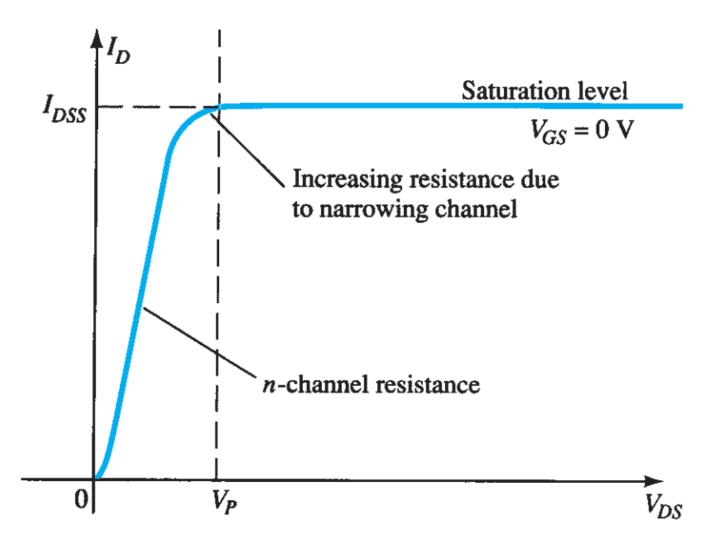
$$V_{
m GS}=0~{
m V}$$
 & $V_{
m DS}>0~{
m V}$



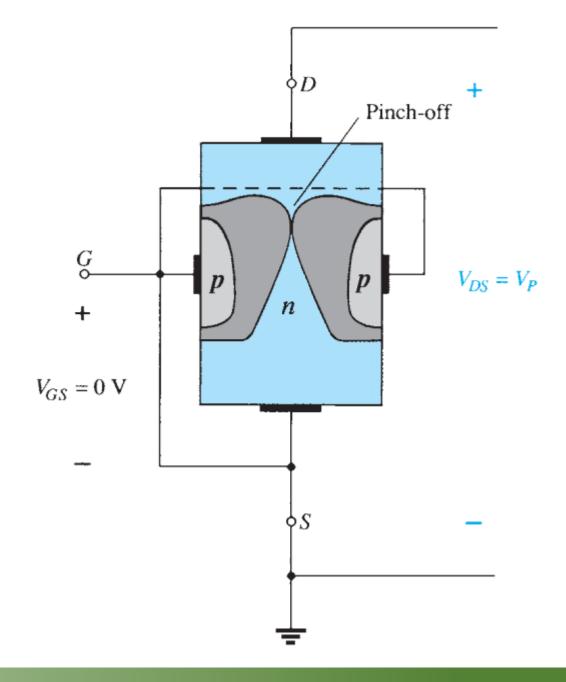
Varying reverse-bias potentials across the p—n junction of an n-channel JFET



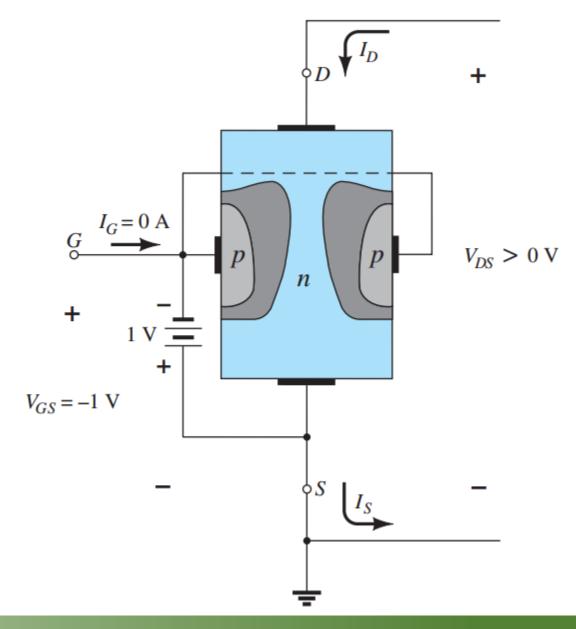
 $I_{\rm D}$ versus $V_{\rm DS}$ for $V_{\rm GS}=0~{\rm V}$



Pinch-off $(V_{GS} = 0 \text{ V}, V_{DS} = V_{P})$

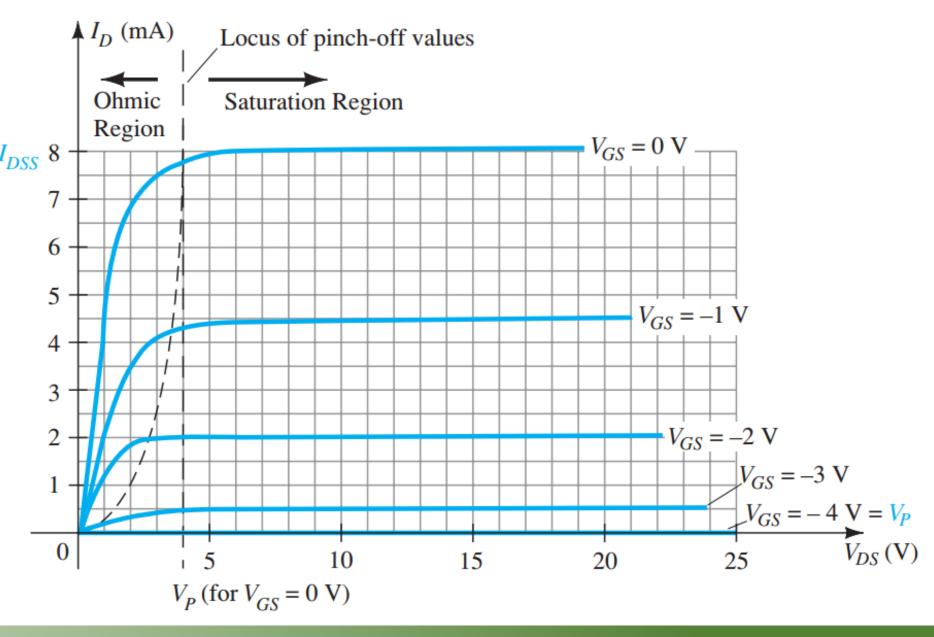


Application of a negative voltage to the gate of a JFET



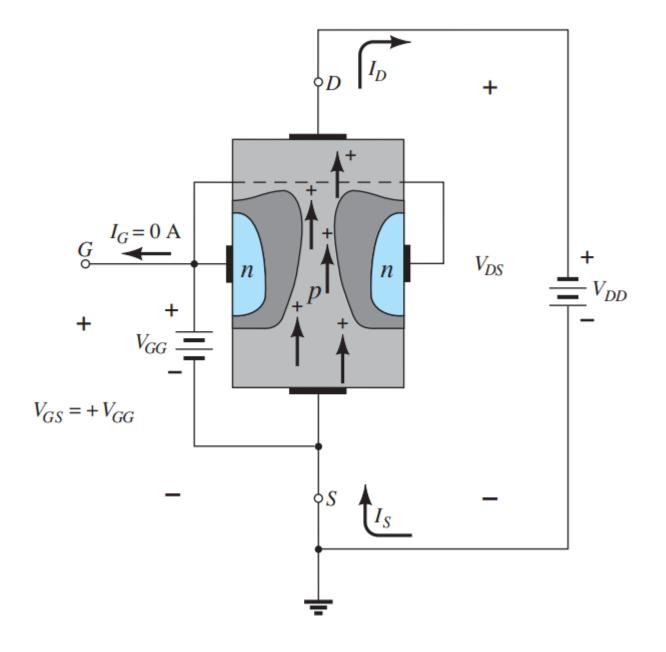


n-Channel JFET characteristics with $I_{DSS} = 8 \text{ mA}$ and $V_P = -4 \text{ V}$



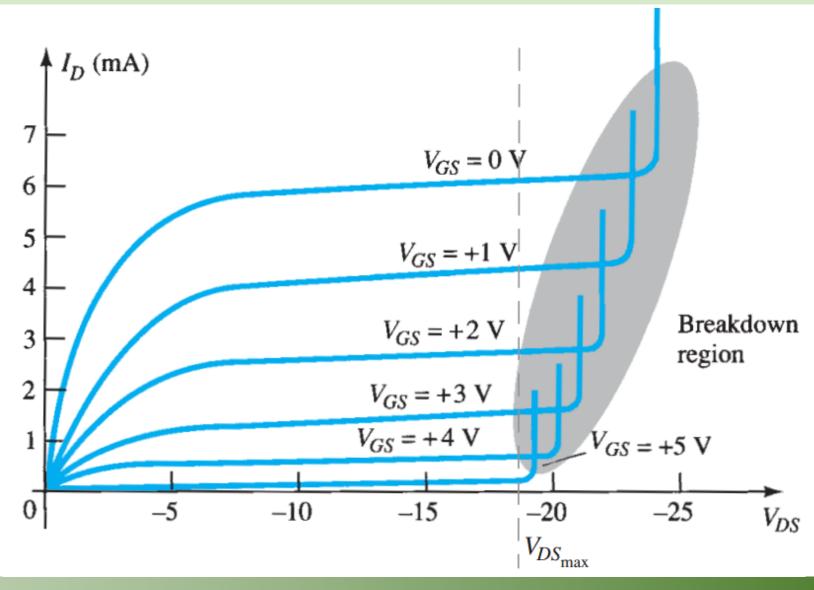


p-Channel JFET



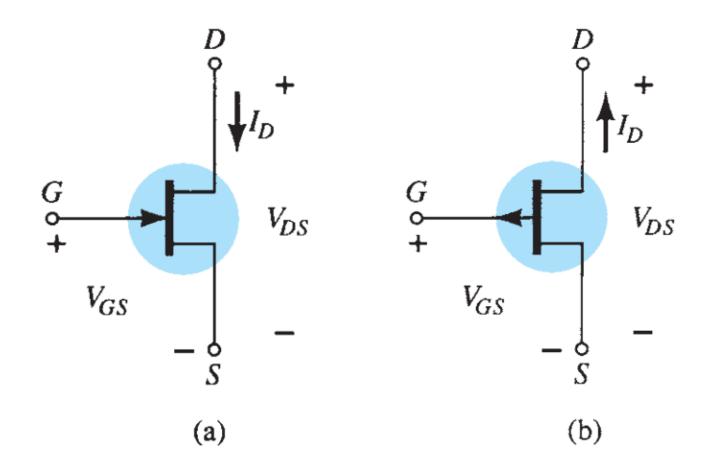


p-Channel JFET characteristics with $I_{DSS} = 6$ mA and $V_P = +6$ V

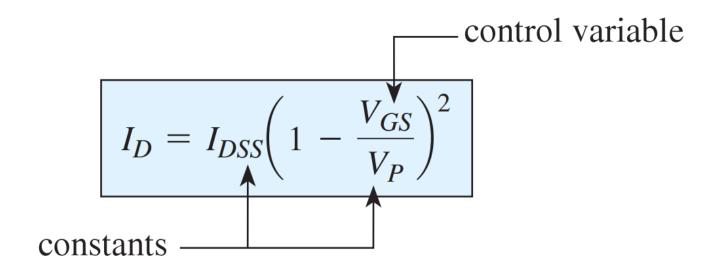




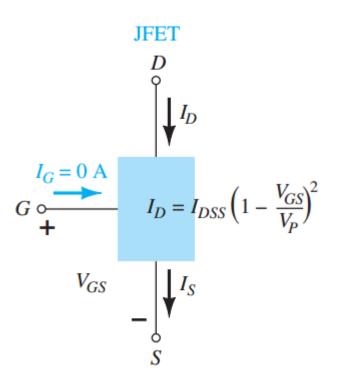
JFET symbols: (a) *n*-channel; (b) *p*-channel

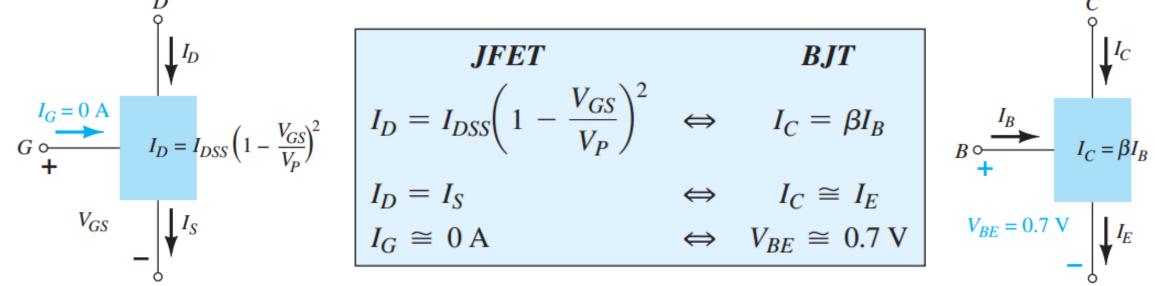


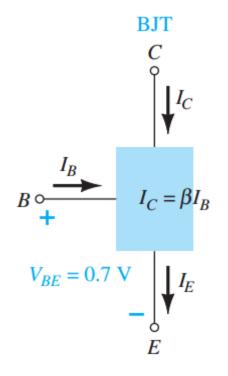
Shockley's equation



$$r_d = \frac{r_o}{(1 - V_{GS}/V_P)^2}$$



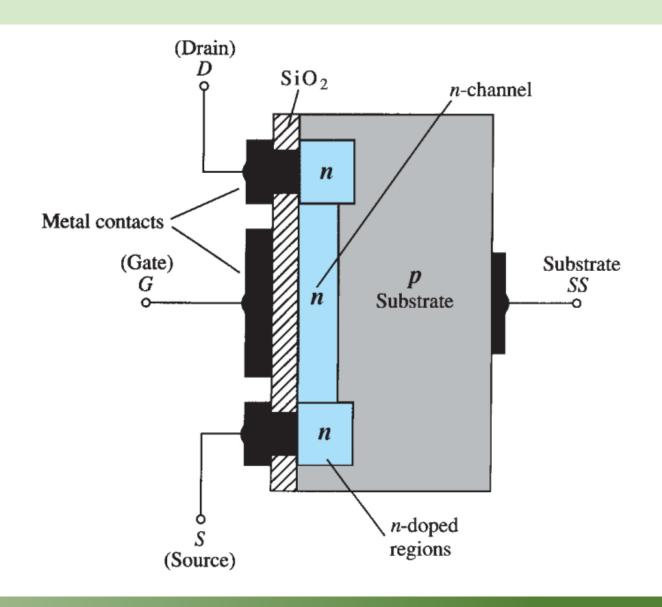




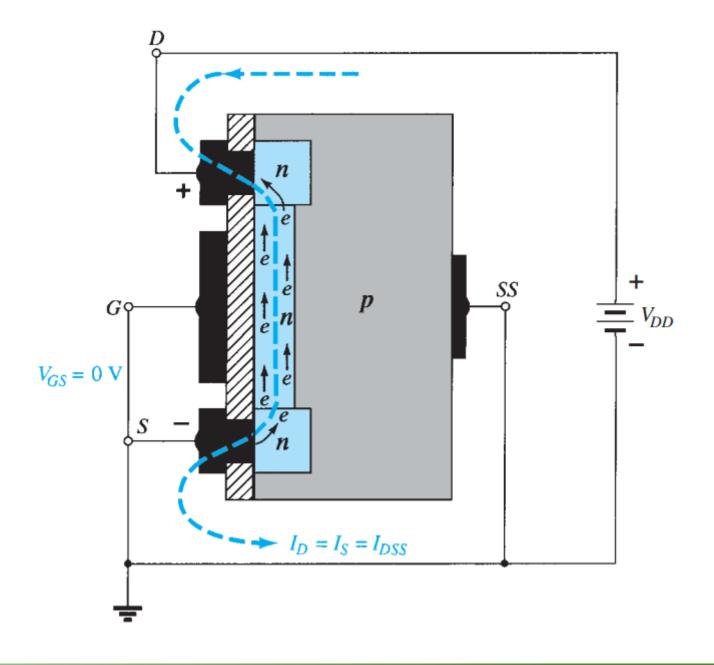
Metal-oxide-semiconductor field-effect transistor (MOSFET)

There is no direct electrical connection between the gate terminal and the channel of a MOSFET

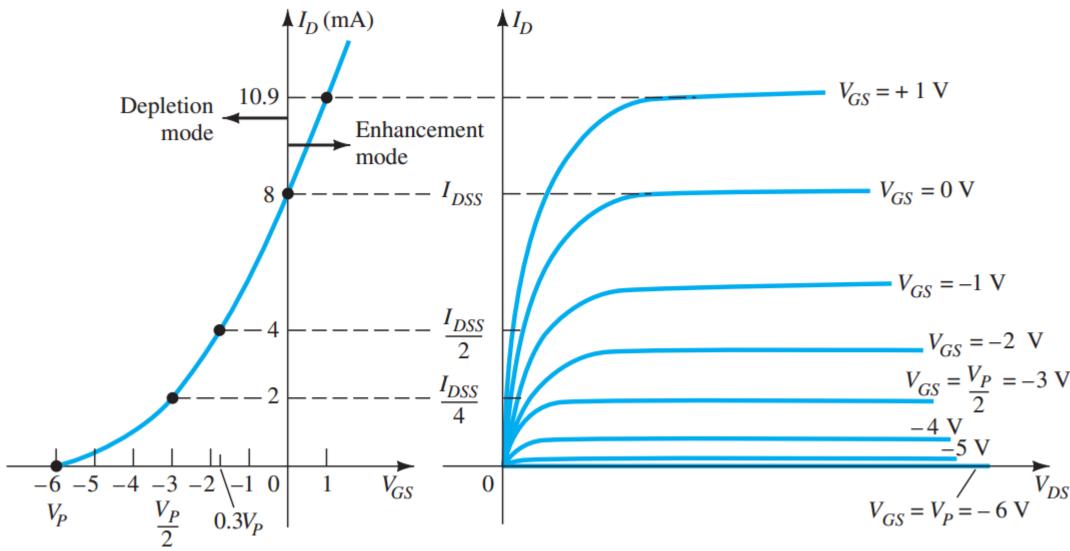
depletion type MOSFET enhancement type MOSFET



n-Channel depletiontype MOSFET with $V_{\rm GS} = 0$ V and applied voltage $V_{\rm DD}$

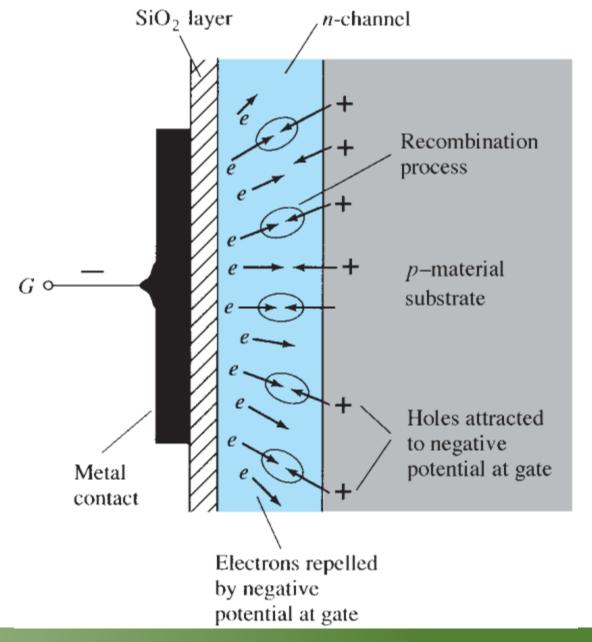


Drain and transfer characteristics for an *n*-channel depletion-type MOSFET



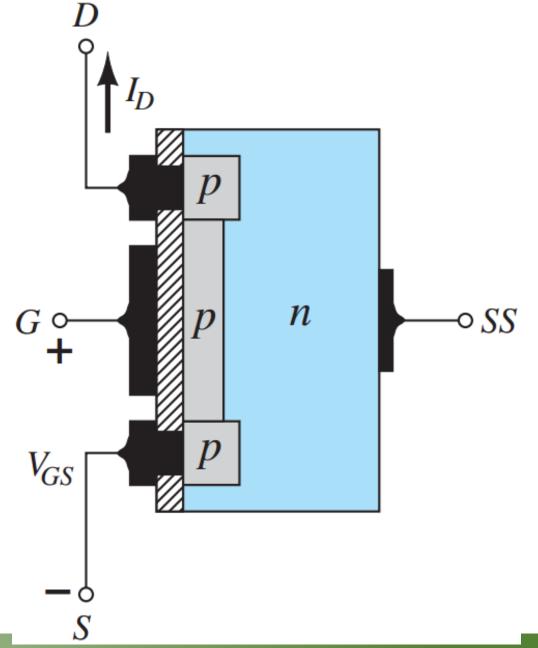


Reduction in free carriers in a channel due to a negative potential at the gate terminal



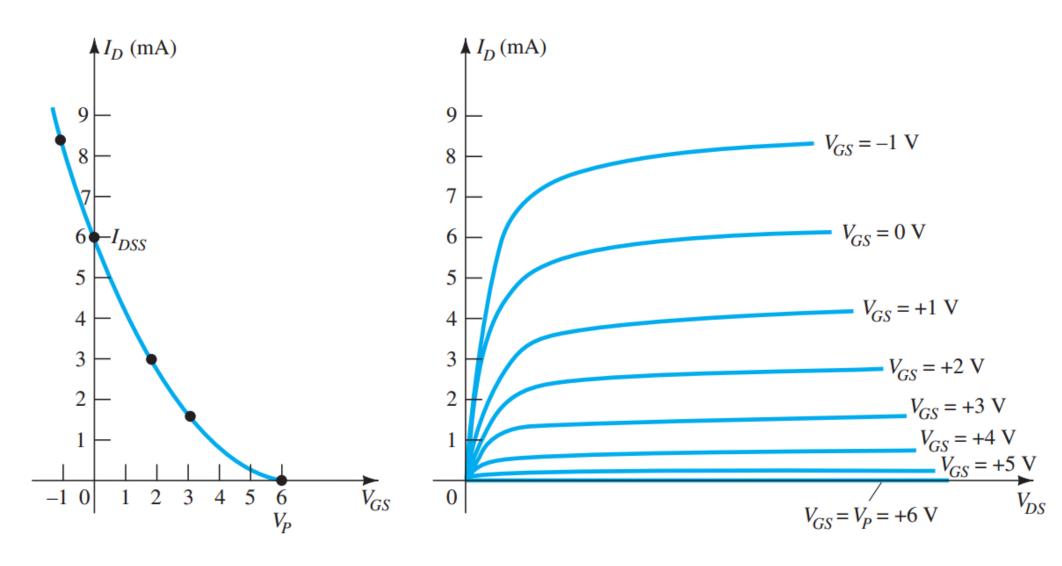


p-channeldepletion-typeMOSFET



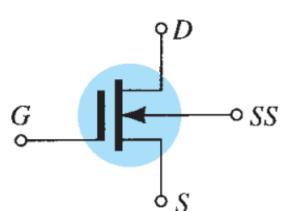


p-channel depletion-type MOSFET

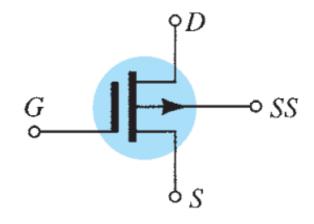




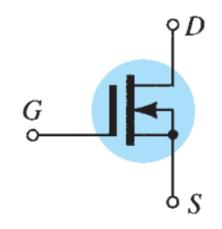
n-channel

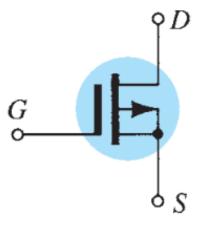


p-channel



Graphic symbols for:
(a) n-channel
depletion-type
MOSFETs and
(b) p-channel
depletion-type
MOSFETs

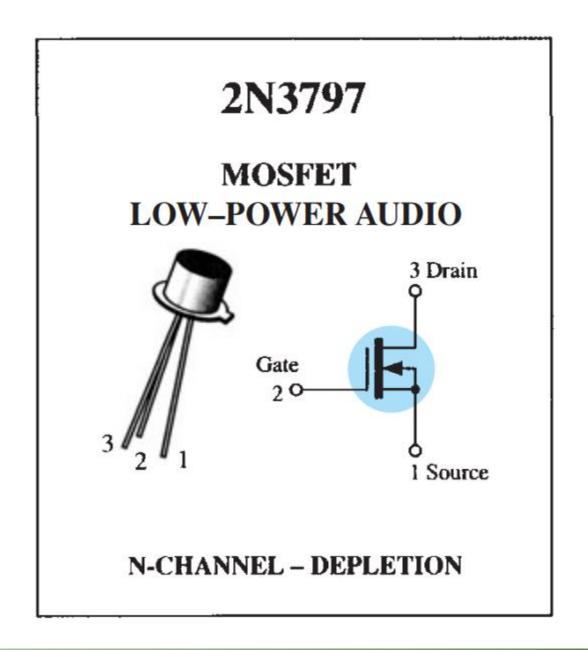




(a)

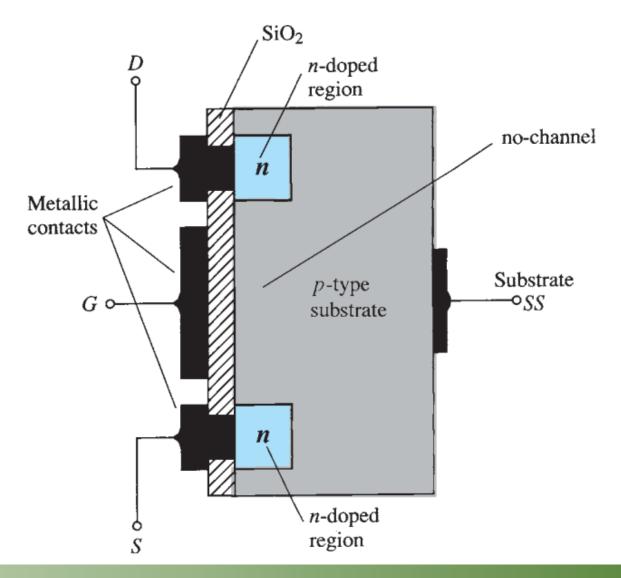
(b)





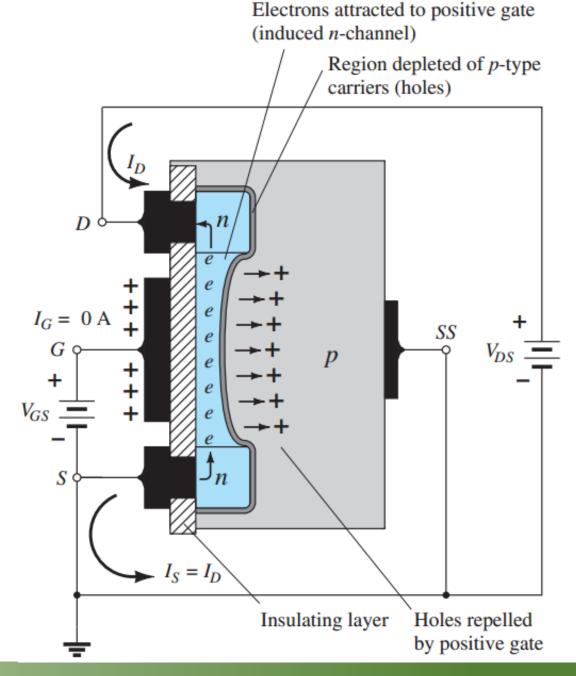


n-Channel enhancement-type MOSFET





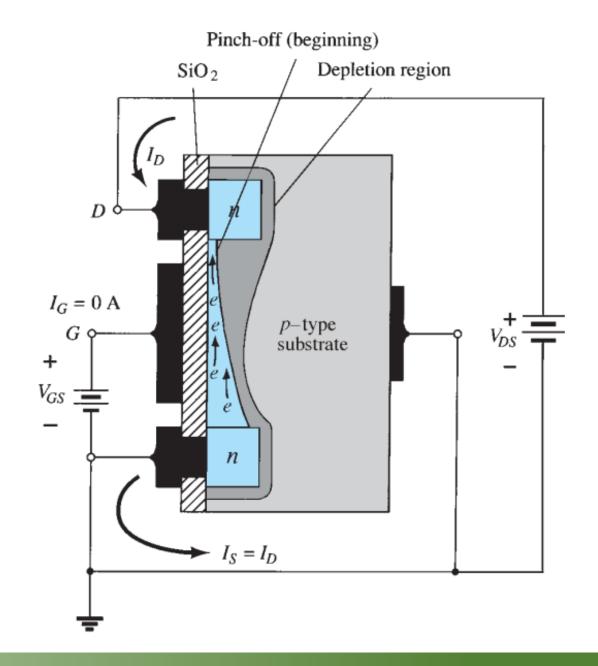
Channel formation in the n-channel enhancement-type MOSFET

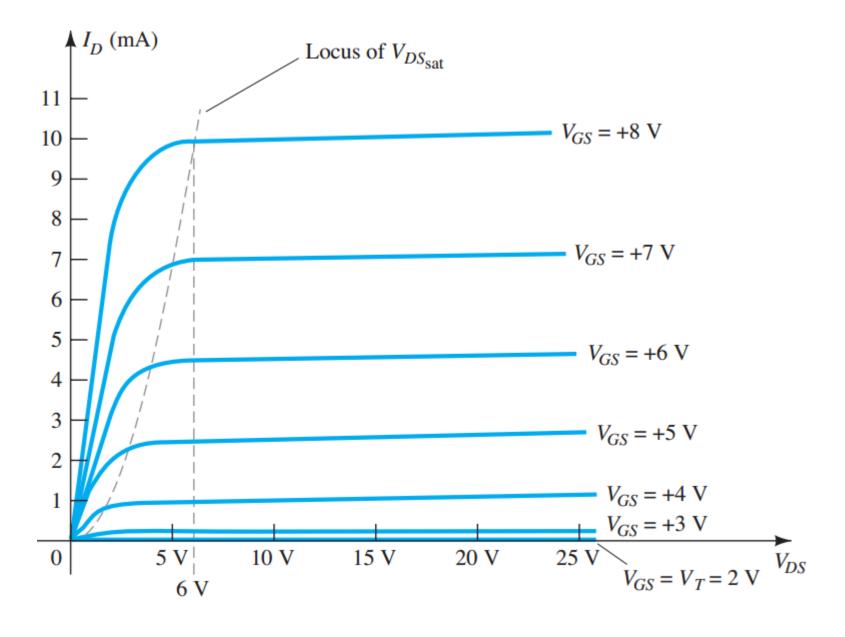


Change in channel and depletion region with increasing level of $V_{\rm DS}$ for a fixed value of $V_{\rm GS}$

$$V_{DG} = V_{DS} - V_{GS}$$

$$V_{DS_{\rm sat}} = V_{GS} - V_T$$





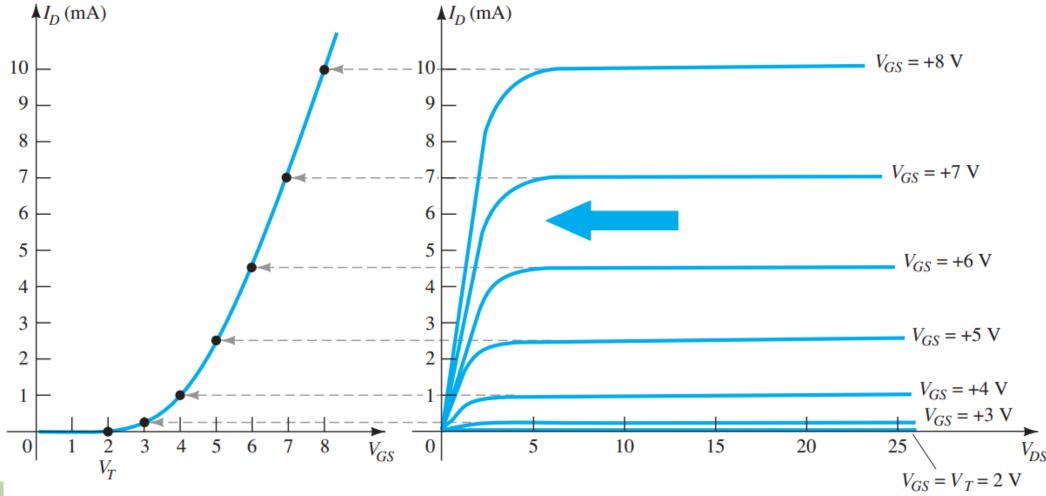
Drain characteristics of an n-channel enhancement-type MOSFET

$$k = 0.278 \times 10^{-3} \, A/V^2$$

$$I_D = k(V_{GS} - V_T)^2$$

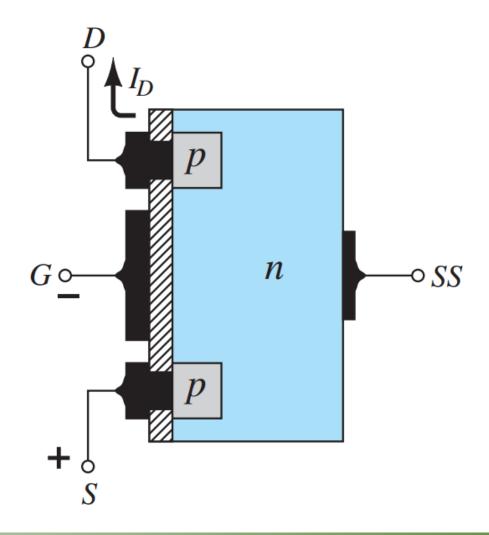
$$k = \frac{I_{D(\text{on})}}{(V_{GS(\text{on})} - V_T)^2}$$

Transfer characteristics for an n-channel enhancement-type MOSFET from the drain characteristics





p-Channel enhancement-type MOSFET



Symbols for:

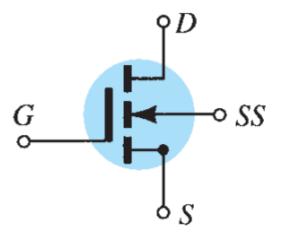
(b) p-channel

MOSFETs

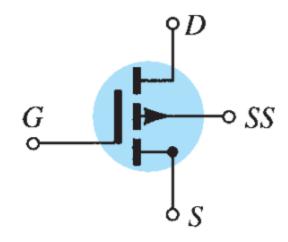
(a) n-channel enhancement-type MOSFETs and

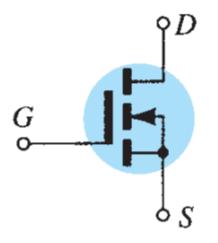
enhancement-type

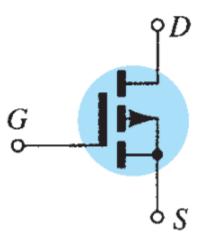
n-channel



p-channel









Readings

Electronic Devices and Circuit Theory

- Boylestad, Nashelsky

Chapter 6: Field-Effect Transistors

